

Docket No.: P2001,0387

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : GABRIELE FICHTL ET AL.
Filed : CONCURRENTLY HEREWITH
Title : METHOD FOR MANUFACTURING A TRENCH CAPACITOR
HAVING AN ISOLATION TRENCH

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In accordance with 37 C.F.R. 1.98 copies of the following patents and/or publications are submitted herewith:

U.S. Patent No. 5,871,659 (Sakano et al.), dated February 16, 1999;

U.S. Patent No. 5,719,080 (Kenney), dated February 17, 1998;

U.S. Patent No. 6,221,784 B1 (Schmidt et al.), dated April 24, 2001;

U.S. Patent No. 5,998,821 (Hieda et al.), dated December 7, 1999;

U.S. Patent No. 5,423,941 (Komura et al.), dated June 13, 1995;

U.S. Patent No. 6,583,020 B2 (Uhlig et al.), dated June 24, 2003 and corresponding PCT WO 00/54326 (Uhlig et al.), dated September 14, 2000;

Patent Abstracts of Japan 63240027 A (Takeshi), dated October 5, 1988;

Patent Abstracts of Japan 10022271 A (Riichi), dated January 23, 1998;

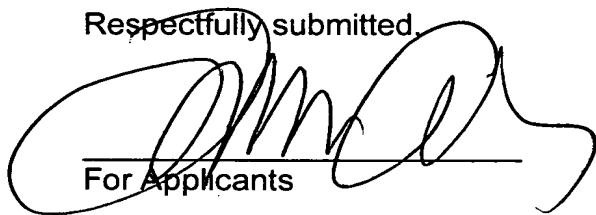
European Patent Application EP 0 819 786 A2 (Zhao et al.), dated January 21, 1998;

Author not listed: "Process for Simultaneously Forming Poly/EPI Silicon Filled Deep and Shallow Isolation Trenches Having a CVD Oxide Cap", IBM Technical Disclosure Bulletin, IBM Corp., Vol. 33, No. 7, December 1990 pp. 388-392;

International Search Report, dated July 11, 2002.

If no translation of pertinent portions of any foreign language patents or publications mentioned above is included with the aforementioned copies of those applications, patents and/or publications, it is because no existing translation is readily available to the applicant. As per the Notice in 1273 OG 55 (August 5, 2003) no copies of any above-mentioned U.S. patents and U.S. patent application publications are submitted for any application filed after June 30, 2003.

Respectfully submitted,



For Applicants

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Date: November 17, 2003

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/nt/kf

FORM PTO-1449 (SUBSTITUTE)		Attorney Docket No.: P2001,0387 Appl. No.:	
U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE			
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (37 CFR 1.98(b))		Applicant: GABRIELE FICHTL ET AL.	
		Filing Date: November 17, 2003 Group Art Unit:	

EXAMINER INITIALS		PATENT NO.	DATE	PATENTEE	CLASS	SUB CLASS	FILING DATE
	A	5,871,659	2/16/99	Sakano et al.			
	B	5,719,080	2/17/98	Kenney			
	C	6,221,784 B1	4/24/01	Schmidt et al.			
	D	5,998,821	12/7/99	Hieda et al.			
	E	5,423,941	6/13/95	Komura et al.			
	F	6,583,020 B2	6/24/03	Uhlig et al.			
	G						
	H						
	I						

FOREIGN PATENT DOCUMENT

		DOCUMENT NO.	DATE	COUNTRY	CLASS	SUB CLASS	TRANSL. YES NO
	J	00/54326	9/14/00	WIPO			
	K	63240027	10/5/88	Japan			
	L	10022271	1/23/98	Japan			
	M	0 819 786 A2	1/21/98	Europe			
	N						

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

		Author not listed: "Process for Simultaneously Forming Poly/EPI Silicon Filled Deep and Shallow Isolation Trenches Having a CVD Oxide Cap", IBM Technical Disclosure Bulletin, IBM Corp., Vol. 33, No. 7, December 1990 pp. 388-392

EXAMINER	DATE CONSIDERED